Pt. 63, Subpt. MMM, Table 2

Reference to subpart A	Applies to subpart MMM	Explanation
§ 63.8(f)(5) § 63.8(f)(6) § 63.8(g) § 63.9(a)—(d) § 63.9(e)	Yes No No Yes	Subpart MMM does not require CEM's. § 63.1366 specifies data reduction procedures.
§ 63.9(f)	No No Yes	Subpart MMM does not contain opacity and visible emission standards.
§ 63.9(h)(2)(i) § 63.9(h)(2)(ii)	Yes	Except § 63.1368(a)(1) specifies additional information to include in the Notification of Compliance Status report. § 63.1368 specifies the Notification of Compliance Status report is to be sub-
§ 63.9(h)(3) § 63.9(h)(4) § 63.9(h)(5)–(6)	Yes N/A Yes	mitted within 150 days after the compliance date. Reserved.
63.9(j)	Yes. No Yes No	§ 63.1368(h) specifies procedures for notification of changes. § 63.1367 specifies recordkeeping requirements.
§ 63.10(b)(3) § 63.10(c) § 63.10(d)(1)	Yes Yes Yes	903.1007 Specifies recordinesping requirements.
§ 63.10(d)(2) § 63.10(d)(3) § 63.10(d)(4)	Yes No Yes	Subpart MMM does not include opacity and visible emission standards.
§ 63.10(d)(5) § 63.10(e)(1)–(2)(i)	Yes	Except that actions and reporting for batch processes do not apply during start- up and shutdown.
§ 63.10(e)(2)(ii) § 63.10(e)(3) § 63.10(e)(4)	No Yes No	Subpart MMM does not include opacity monitoring requirements. Subpart MMM does not include opacity monitoring requirements.
§ 63.10(f) § 63.11–§ 63.15	Yes Yes.	

 $[64\;\mathrm{FR}\;33589,\,\mathrm{June}\;23,\,1999,\,\mathrm{as}\;\mathrm{amended}\;\mathrm{at}\;67\;\mathrm{FR}\;59355,\,\mathrm{Sept.}\;20,\,2002]$

Table 2 to Subpart MMM of Part 63—Standards for New and Existing PAI Sources

Applicability sting: rrocesses having uncontrolled organic HAP missions ≥0.15 Mg/yr. rrocesses having uncontrolled HCl and chlo- ne emissions ≥6.8 Mg/yr. ndividual process vents meeting flow and nass emissions criteria that have gaseous rganic HAP emissions controlled to less	concentration of ≤20 ppmv TOC. 94% for HCl and chlorine per process or to outlet HCl and chlorine concentration of ≤20 ppmv. 98% gaseous organic HAP control per vent or
rocesses having uncontrolled organic HAP missions ≥0.15 Mg/yr. rocesses having uncontrolled HCl and chlone emissions ≥6.8 Mg/yr. ndividual process vents meeting flow and hass emissions criteria that have gaseous	94% for HCl and chlorine per process or to outlet HCl and chlorine concentration of ≤20 ppmv. 98% gaseous organic HAP control per vent or
nass emissions criteria that have gaseous	
nan 90% on or after November 10, 1997.	≤20 ppmv TOC outlet limit.
w: processes having uncontrolled organic HAP missions ≥0.15 Mg/yr. processes having uncontrolled HCl and chlo- ne emissions ≥6.8 Mg/yr and <191 Mg/yr.	98% for organic HAP per process or ≤20 ppmv TOC. 94% for HCl and chlorine per process or to outlet concentration of ≤20 ppmv HCl and chlorine.
cesses having uncontrolled HCl and chlone emissions $\geq 191~\text{Mg/yr}.$	99% for HCl and chlorine per process or to outlet concentration of ≤20 ppmv HCl and chlorine.
sting: ≥75 m³ capacity and vapor pressure 3.45 kPa.	Install a floating roof, reduce HAP by 95% per vessel, or to outlet concentration of ≤20 ppmv TOC.
w: ≥38 m³ capacity and vapor pressure 16.5 kPa.	Same as for existing sources.
i m³ capacity and vapor pressure ≥3.45 kPa sting: Process wastewater with ≥10,000 pmw Table 9 compounds at any flowrate or 1,000 ppmw Table 9 compounds at ≥10 LV nin, and maintenance wastewater with HAP and ≥5.3 Mg per discharge event.	Same as for existing sources. Reduce concentration of total Table 9 compounds to <50 ppmw (or other options).
TAPE OF SECTO	an 90% on or after November 10, 1997. v. rocesses having uncontrolled organic HAP missions ≥0.15 Mg/yr. rocesses having uncontrolled HCl and chlone emissions ≥6.8 Mg/yr and <191 Mg/yr. cesses having uncontrolled HCl and chlone emissions ≥191 Mg/yr. cesses having uncontrolled HCl and chlone emissions ≥191 Mg/yr. sting: ≥75 m³ capacity and vapor pressure 3.45 kPa. v: ≥38 m³ capacity and vapor pressure 16.5 kPa. m³ capacity and vapor pressure ≥3.45 kPa sting: Process wastewater with ≥10,000 pmw Table 9 compounds at any flowrate or 1,000 pmw Table 9 compounds at ≥10 L/ in, and maintenance wastewater with HAP

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Pt. 63, Subpt. MMM, Table 3

Emission source	Applicability	Requirement	
	Same criteria as for existing sources	Reduce concentration of total Table 9 compounds to <50 ppmw (or other options).	
	Total HAP load in wastewater POD streams ≥2,100 Mg/yr	99% reduction of Table 9 compounds from all streams.	
Equipment leaks	Subpart H	Subpart H with minor changes, including moni- toring frequencies consistent with the pro- posed CAR.	
Product dryers and bag dumps.	Dryers used to dry PAI that is also a HAP, and bag dumps used to introduce feedstock that is a solid and a HAP.	Particulate matter concentration not to exceed 0.01 gr/dscf.	
Heat exchange systems	Each heat exchange system used to cool proc- ess equipment in PAI manufacturing oper- ations.	Monitoring and leak repair program as in HON.	

^a Table 9 is listed in the appendix to subpart G of 40 CFR part 63.

Table 3 to Subpart MMM of Part 63—Monitoring Requirements for Control Devices $^{\rm A}$

	22.1	020	
Control device	Monitoring equipment required	Parameters to be monitored	Frequency
All control devices	Flow indicator installed at all bypass lines to the at- mosphere and equipped with continuous recorder or.	Presence of flow diverted from the control device to the atmosphere or.	Hourly records of whether the flow indicator was operating and whether a diversion was detected at any time during each hour. Monthly.
	Valves sealed closed with car-seal or lock-and-key configuration.	Monthly inspections of sealed valves.	
Scrubber	Liquid flow rate or pressure drop mounting device. Also a pH monitor if the scrub- ber is used to control acid emissions	Liquid flow rate into or out of the scrubber or the pres- sure drop across the scrub- ber	1. Every 15 minutes.
		pH of effluent scrubber liq- uid.	2. Once a day.
Thermal incinerator	Temperature monitoring device installed in firebox or in ductwork immediately downstream of firebox b.	Firebox temperature	Every 15 minutes.
Catalytic incinerator	Temperature monitoring de- vice installed in gas stream immediately before and after catalyst bed.	Temperature difference across catalyst bed.	Every 15 minutes.
Flare	Heat sensing device installed at the pilot light.	Presence of a flame at the pilot light.	Every 15 minutes.
Boiler or process heater <44 megawatts and vent stream is not mixed with the primary fuel.	Temperature monitoring device installed in firebox b.	Combustion temperature	Every 15 minutes.
Condenser	Temperature monitoring device installed at condenser exit.	Condenser exit (product side) temperature.	Every 15 minutes.
Carbon adsorber (nonregenerative).	None	Operating time since last replacement.	N/A.
Carbon adsorber (regenerative).	Stream flow monitoring device, and.	Total regeneration stream mass or volumetric flow during carbon bed regen- eration cycle(s).	For each regeneration cycle, record the total regeneration stream mass or volumetric flow.
	Carbon bed temperature monitoring device.	Temperature of carbon bed after regeneration.	For each regeneration cycle, record the maximum carbon bed-temperature.
		Temperature of carbon bed within 15 minutes of com- pleting any cooling cycle(s).	Within 15 minutes of com- pleting any cooling cycle, record the carbon bed tem- perature.
		Operating time since end of last regeneration. Check for bed poisoning	Operating time to be based on worst-case conditions. Yearly.

[&]quot;As an alternative to the monitoring requirements specified in this table, the owner or operator may use a CEM meeting the requirements of Performance Specifications 8 or 9 of appendix B of part 60 to monitor TOC every 15 minutes.

^b Monitor may be installed in the firebox or in the ductwork immediately downstream of the firebox before any substantial heat exchange is encountered.